

PATENT APPLICATION
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q93721

Hans-Juergen ROSTALSKI, et al.

Appln. No.: 10/571,267

Group Art Unit: 2873

Confirmation No.: 6099

Examiner: Darryl J. COLLINS

Filed: February 12, 2007

For: LITHOGRAPHY LENS SYSTEM AND PROJECTION EXPOSURE SYSTEM
PROVIDED WITH AT LEAST ONE LITHOGRAPHY LENS SYSTEM OF THIS TYPE

AMENDMENT UNDER 37 C.F.R. § 1.111

MAIL STOP AMENDMENT

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated July 29, 2008, please amend the above-identified application as follows on the accompanying pages.

TABLE OF CONTENTS

AMENDMENTS TO THE CLAIMS	2
REMARKS	8